

METHOD FOR RECYCLING ETCHING SOLUTION

ABSTRACT

Provided is a method that is for recycling an etching solution, in which an etching solution (exhausted solution) that has been used in a semiconductor etching treatment is regenerated, and that is capable of regenerating not only conventional etching solutions but also a high-performance etching solution that is an etching solution containing a silica deposition inhibitor. In this method for recycling an etching solution, an inorganic acid-based etching solution that is or has been used in etching of a semiconductor is regenerated by diffusion dialysis. The method comprises an extraction step of bringing an etching solution containing a dialysis aid into contact with water through an anion-exchange membrane and thereby extracting an inorganic acid contained in the etching solution into the water.

[Fig. 2]